

Depletion depth studies of MALTA2 a 180 nm monolithic active pixel sensor



Vlad Dumitru Berlea, **DESY** and **Humboldt University**

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**13th International “Hiroshima” Symposium
on the Development and Application of
Semiconductor Tracking Detectors (HSTD13)**

HELMHOLTZ

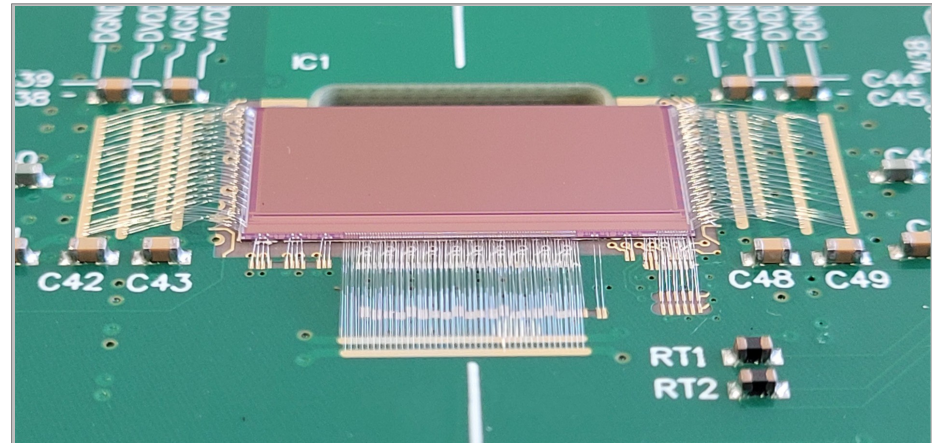


December 3-8 2023

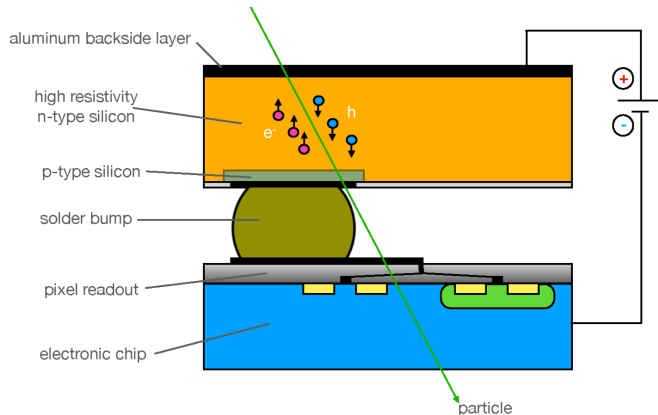
MALTA2 sensor

X Monolithic Active Pixel Sensor

- ◆ 180 nm Tower CMOS process
- ◆ 1 x 2 cm² sensor area
- ◆ 256 x 512 pixels
- ◆ 36.4 x 36.4 μm² pixel size

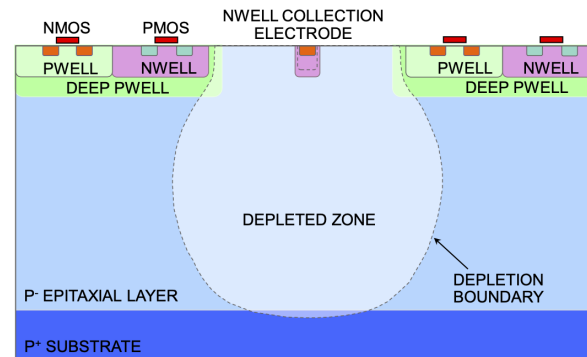


Hybrid Pixel Sensor



ASIC bump bonded to sensor

Monolithic Active Pixel Sensor

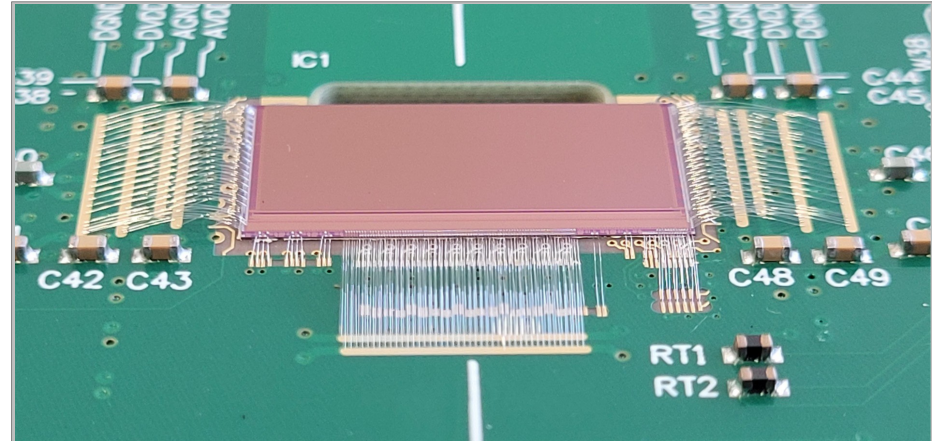


eg. ALPIDE monolithic chip design

MALTA2 sensor

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X Tracking sensor for future collider experiments

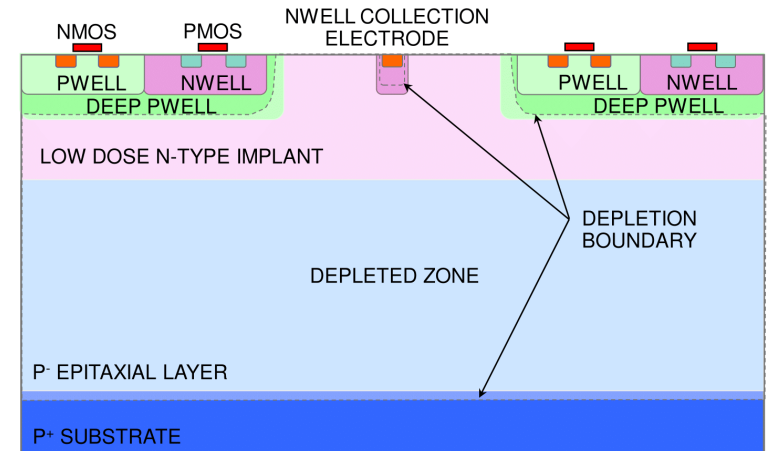
- ◆ Timing response < 2 ns G. Gustavino et al., JINST C03011
- ◆ Radiation hardness up to $3 \times 10^{15} n_{eq}/cm^2$ M. van Rijnbach et al., 2308.13231
- ◆ Low threshold (~150 e) and noise chip operation V. Berlea et al., IEEE TNS 2023.3313721

X Asynchronous readout architecture F. Piro et al., IEEE TNS 19222311

- ◆ No clock propagation across pixel matrix
- ◆ Individual hit information piped to the sensor periphery
- ◆ High data rate (>100 MHz/cm²)
- ◆ No time over threshold information, only binary hit info

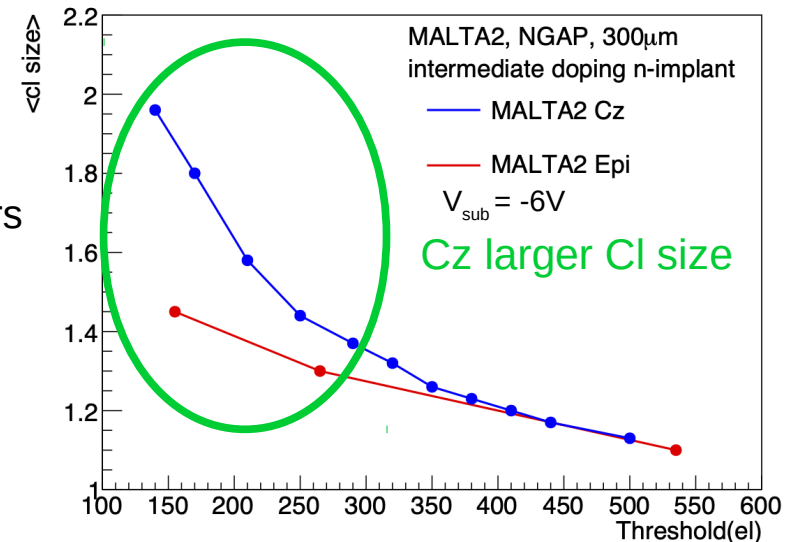
MALTA pixel

- X Small, collection electrode design, $3 \times 3 \mu\text{m}^2$
 - ◆ $< 5 \text{ fF}$ capacitance
 - ◆ $\text{ENC} < 15 e^-$
 - ◆ Low bias voltage (6 – 55 V)
 - ◆ Low power consumption ($1 \mu\text{W}/\text{pixel}$)
 - ◆ Additional low dose N-type implant



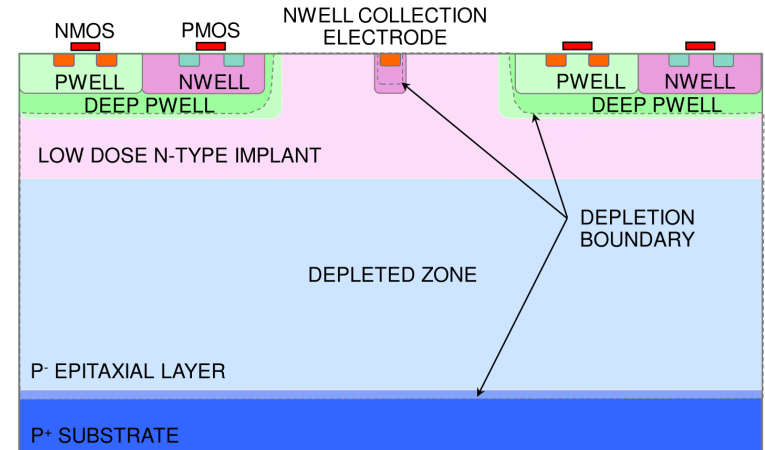
H. Pernegger et al., JINST P09018

- X MALTA samples on multiple substrates
 - ◆ Epitaxial silicon (Epi): $30 \mu\text{m}$
 - ◆ Czochralski silicon (Cz): 300, 100, $50 \mu\text{m}$
 - ◆ Cz: more charge diffusion – larger clusters



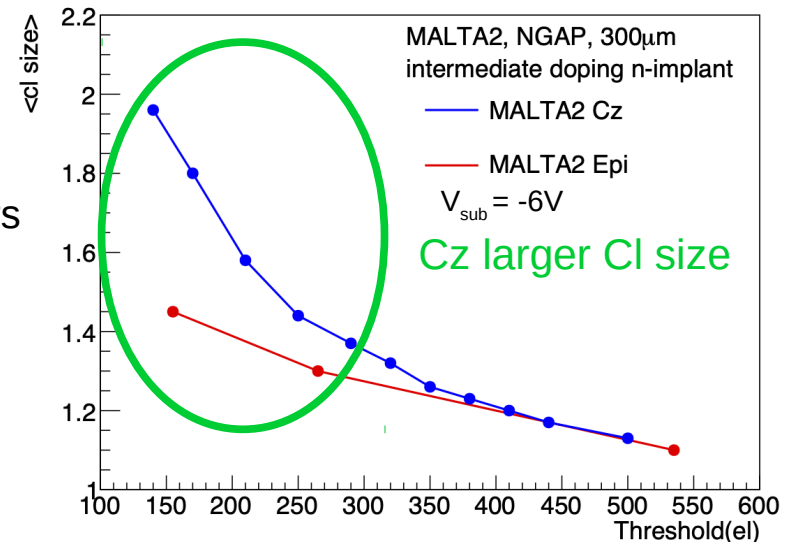
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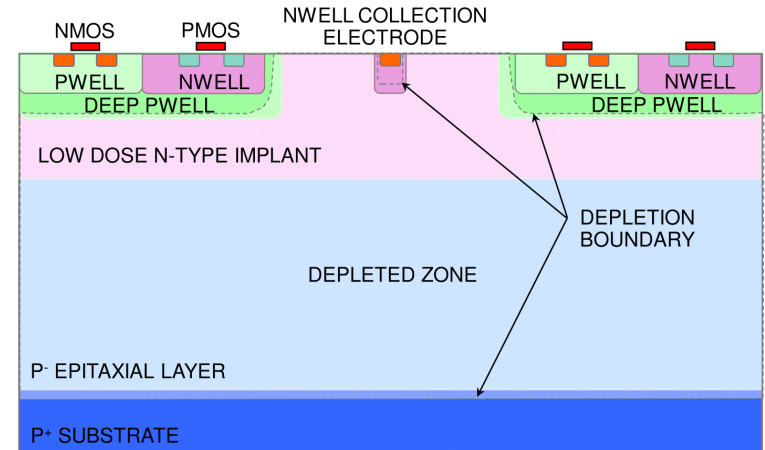


How to measure the depletion depth?

Capacitance measurements
Edge TCT
Grazing angle technique

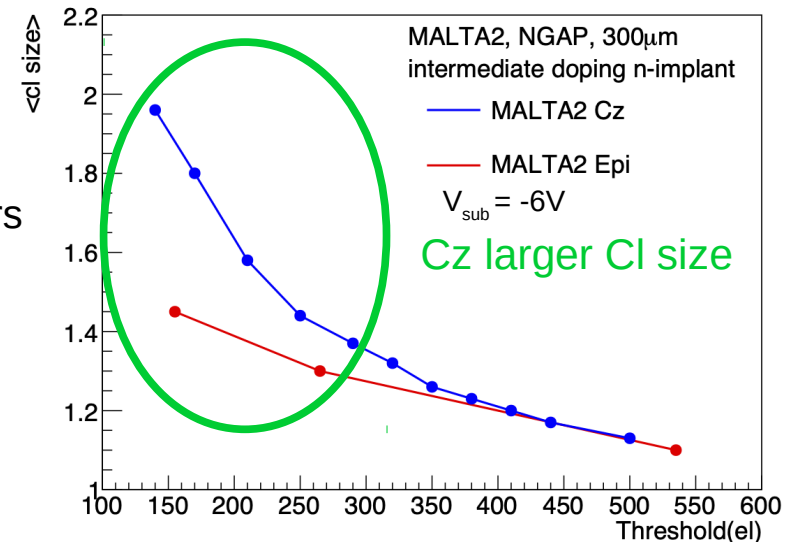
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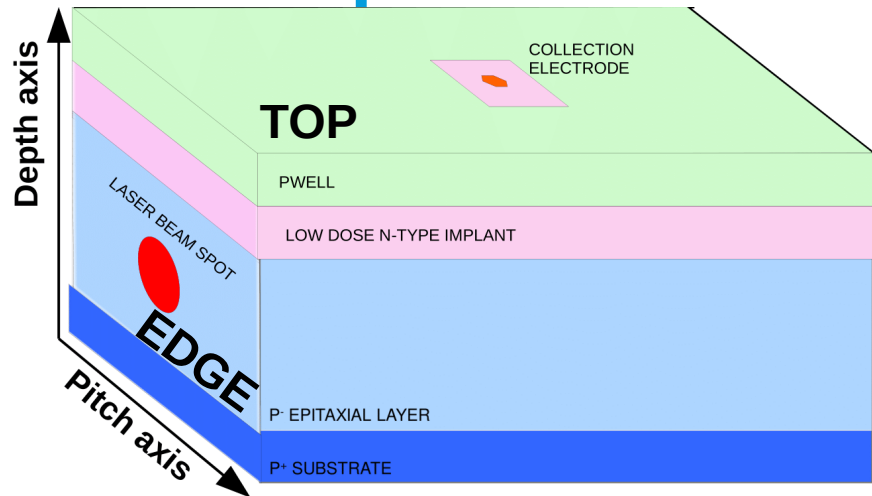


How to measure the depletion depth?

- ✗ Capacitance measurements
- ✓ Edge TCT
- ✓ Grazing angle technique

Edge Transient Current Technique

- x IR pulsed laser:
 - ◆ 1064 nm wavelength
 - ◆ 500 Hz frequency
 - ◆ ~ 4 μm beam width at focus
 - ◆ Sensor edge polish + PCB cut out



- x Precise edge charge injection
 - ◆ Special analog output pixels used
 - ◆ Axis control ~ 0.2 μm precision
 - ◆ Edge scan in 2 axes: Pitch and Depth

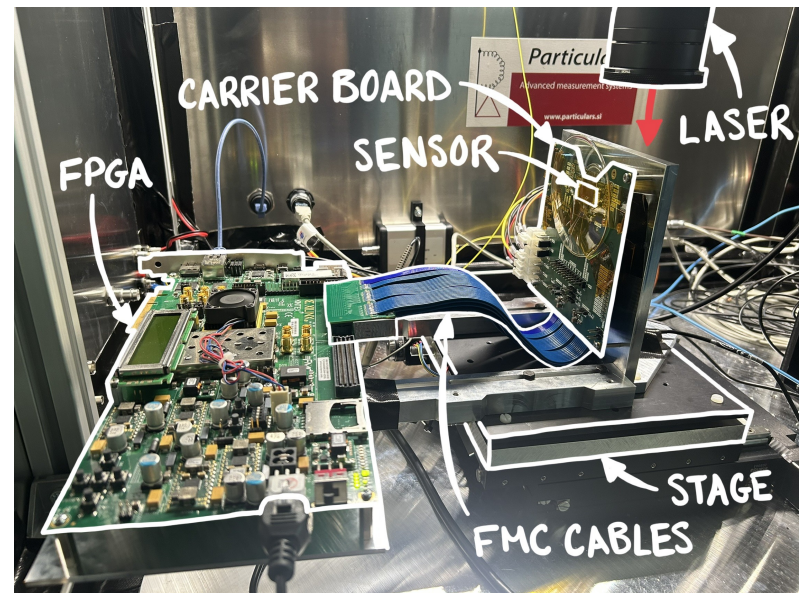
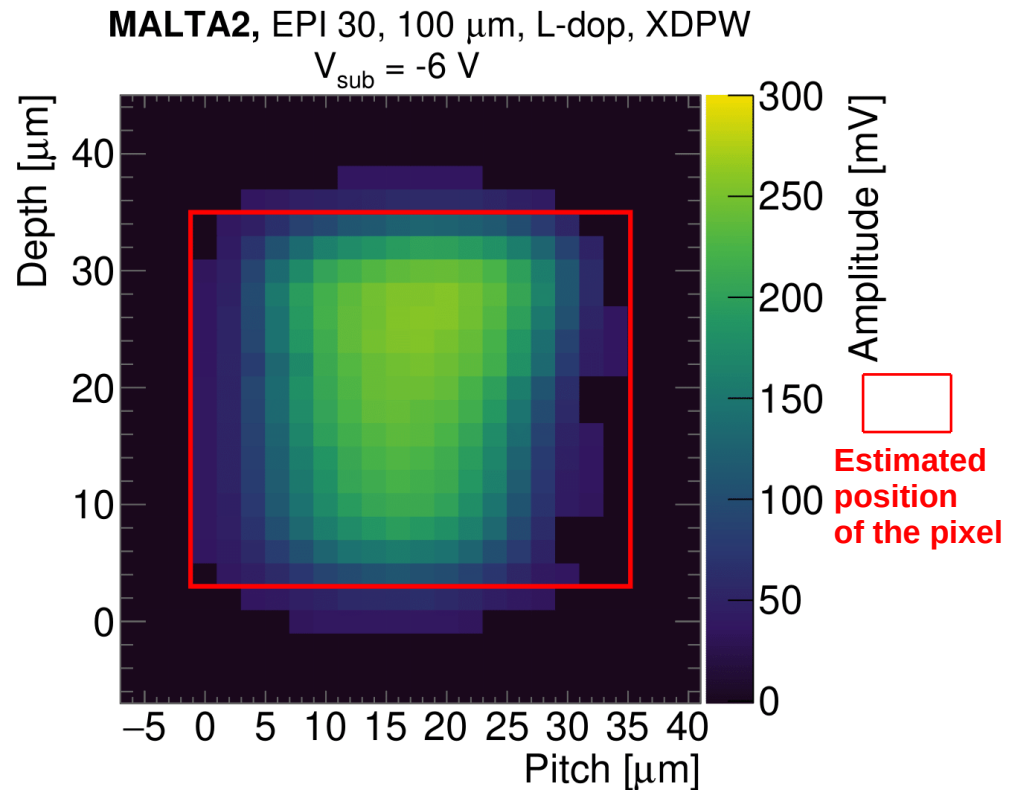
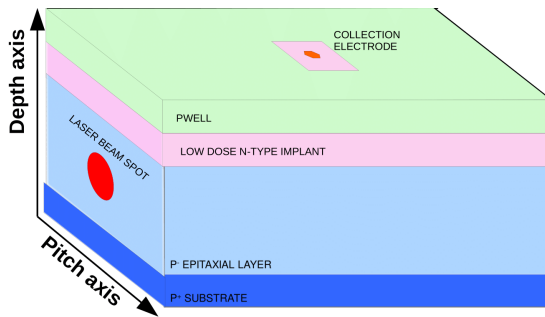


Photo by: Alex Savino, DESY Summer student, 2023

Investigation of Epitaxial sample

X 36.4 μm pitch x $30 \pm 2 \mu\text{m}$ depth pixel edge

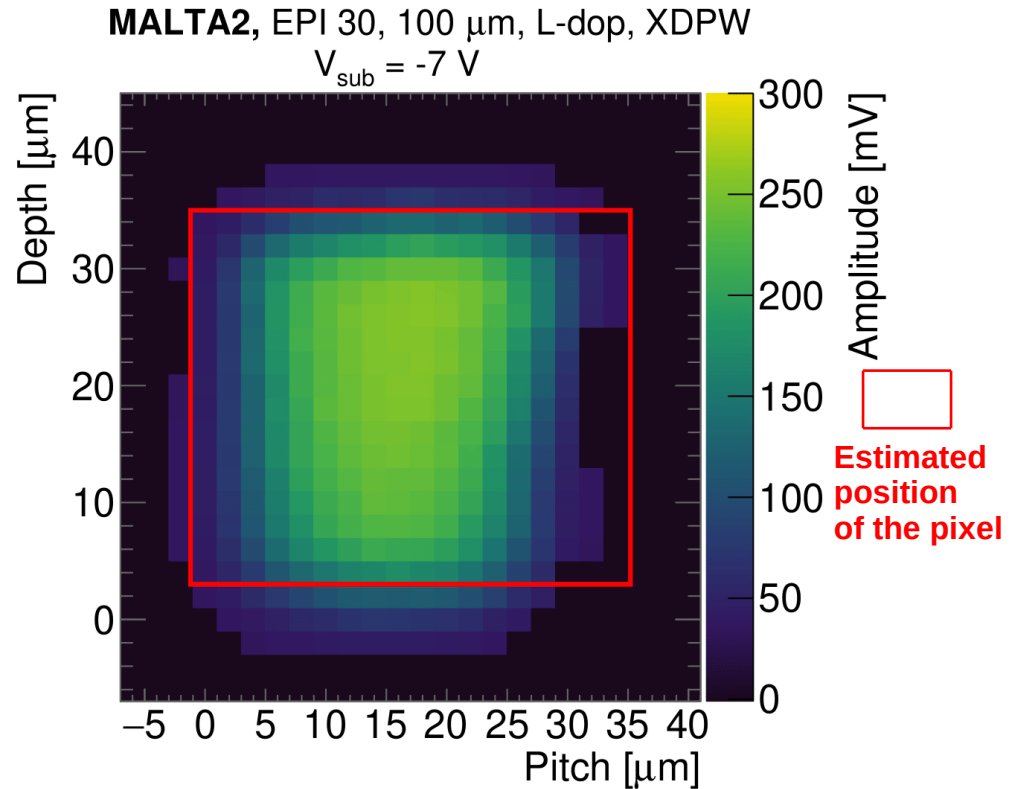
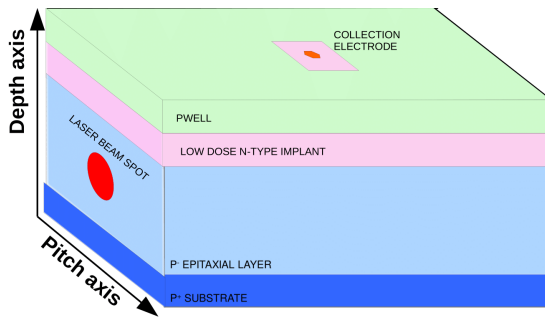
- ◆ Top: Collection electrode
- ◆ Left: Sensor edge
- ◆ Right: Pixel matrix



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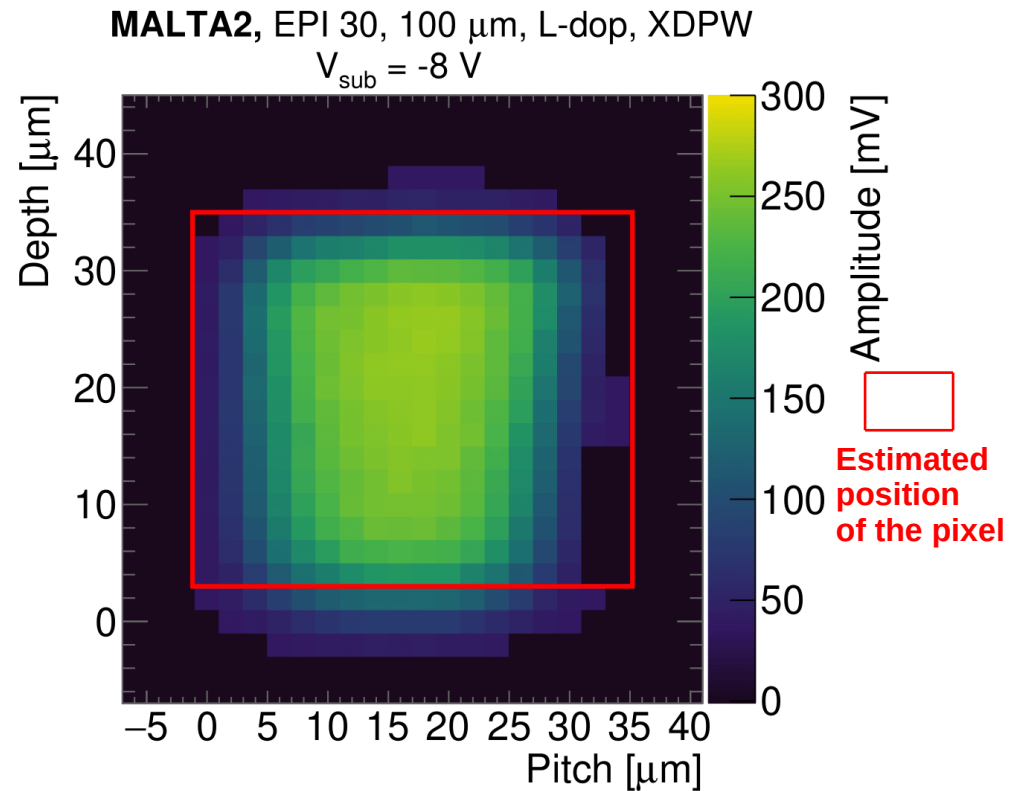
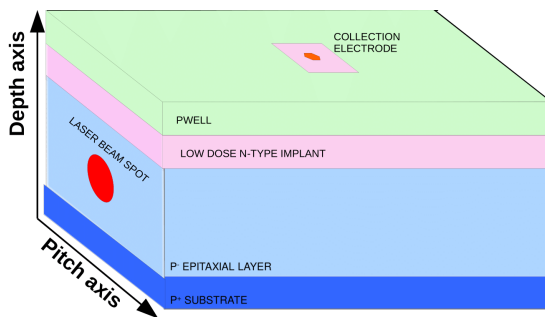
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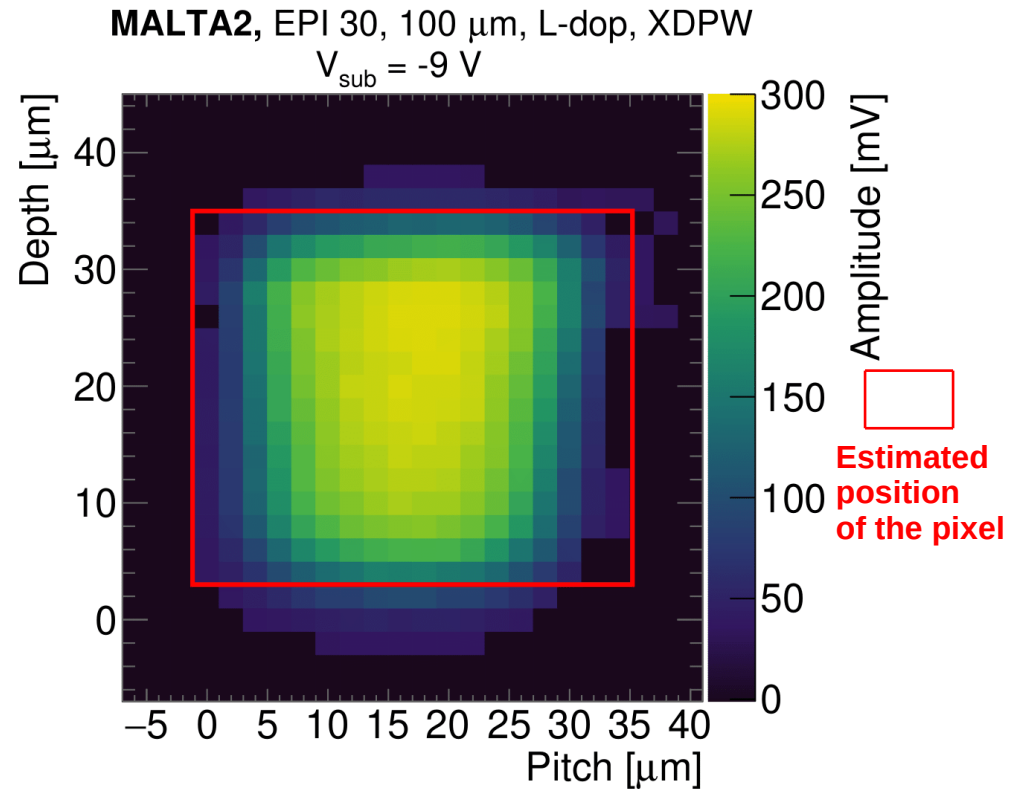
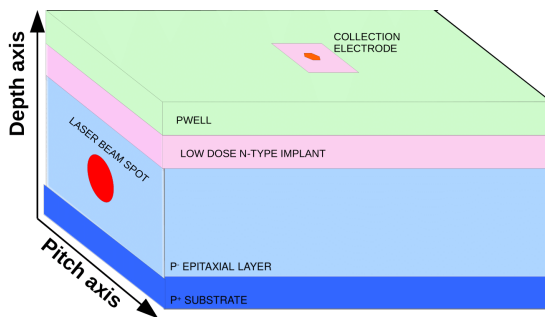
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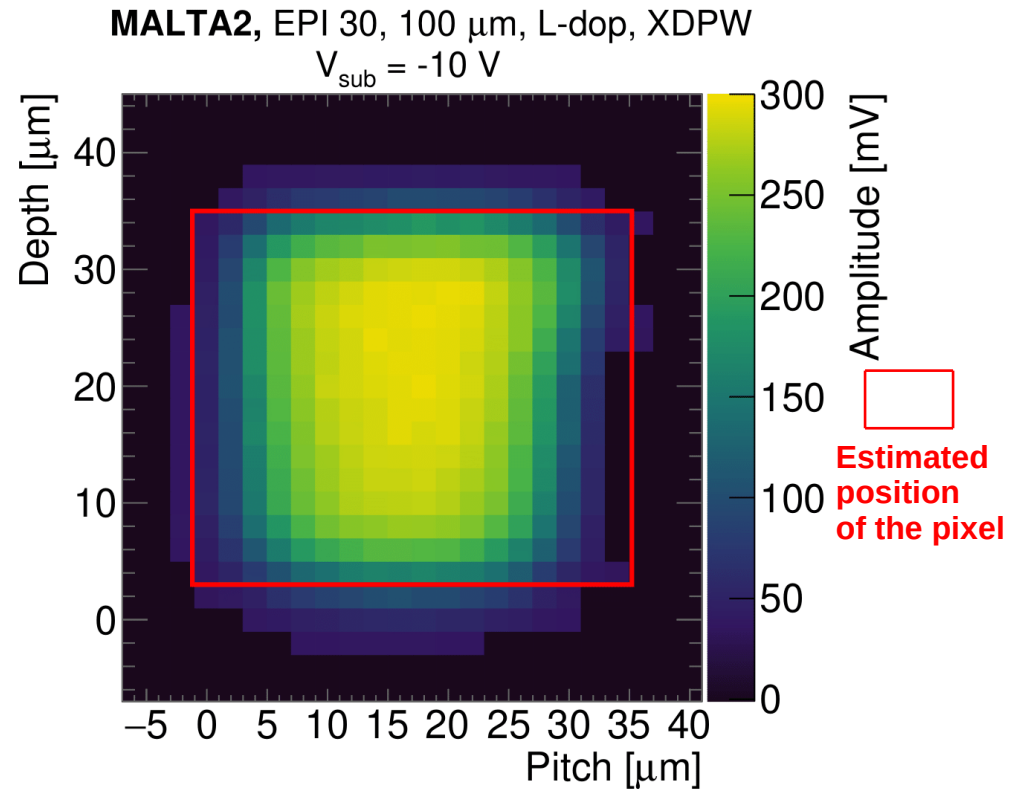
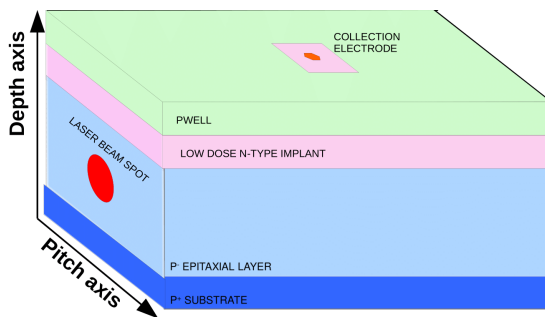
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Investigation of Epitaxial sample

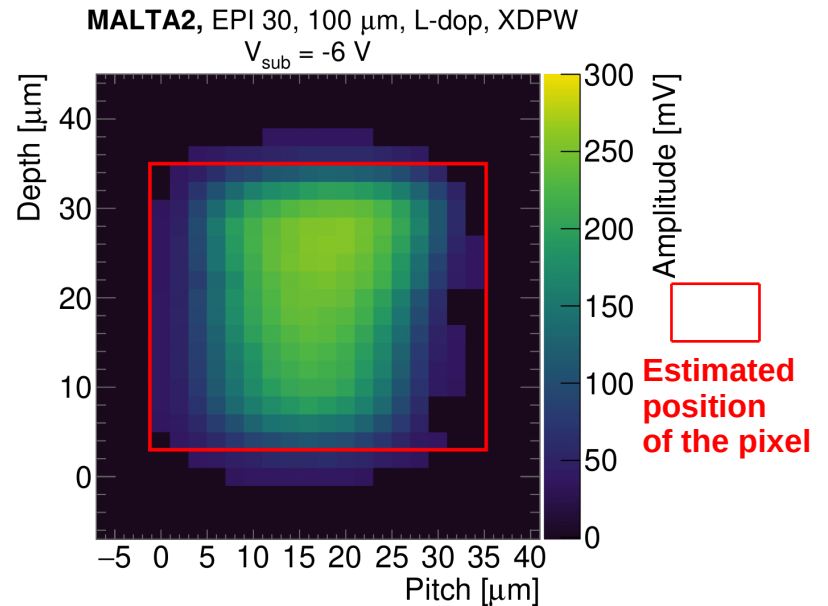
X 36.4 μm pitch x $30 \pm 2 \mu\text{m}$ depth pixel edge

- ◆ Top: Collection electrode
- ◆ Left: Sensor edge
- ◆ Right: Pixel matrix

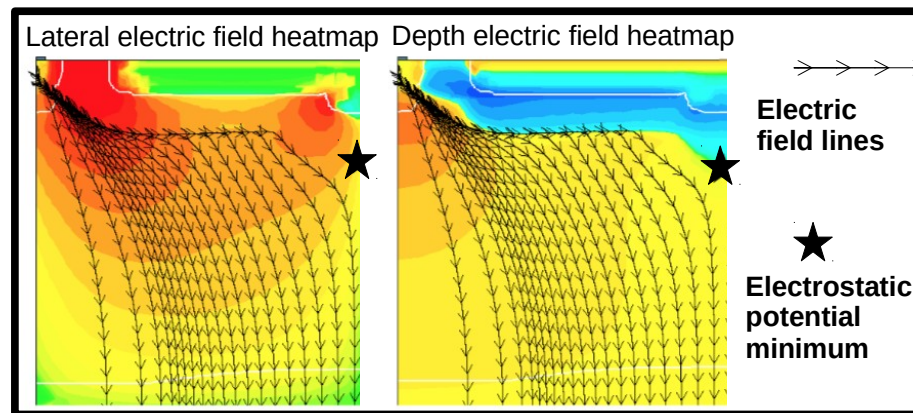


Investigation of Epitaxial sample

- ✗ 36.4 μm pitch x $30 \pm 2 \mu\text{m}$ depth pixel edge
 - ◆ Top: Collection electrode
 - ◆ Left: Sensor edge
 - ◆ Right: Pixel matrix
- ✗ TCAD simulations:
 - ◆ Large E field near the collection electrode
 - ◆ Decreased E field with depth

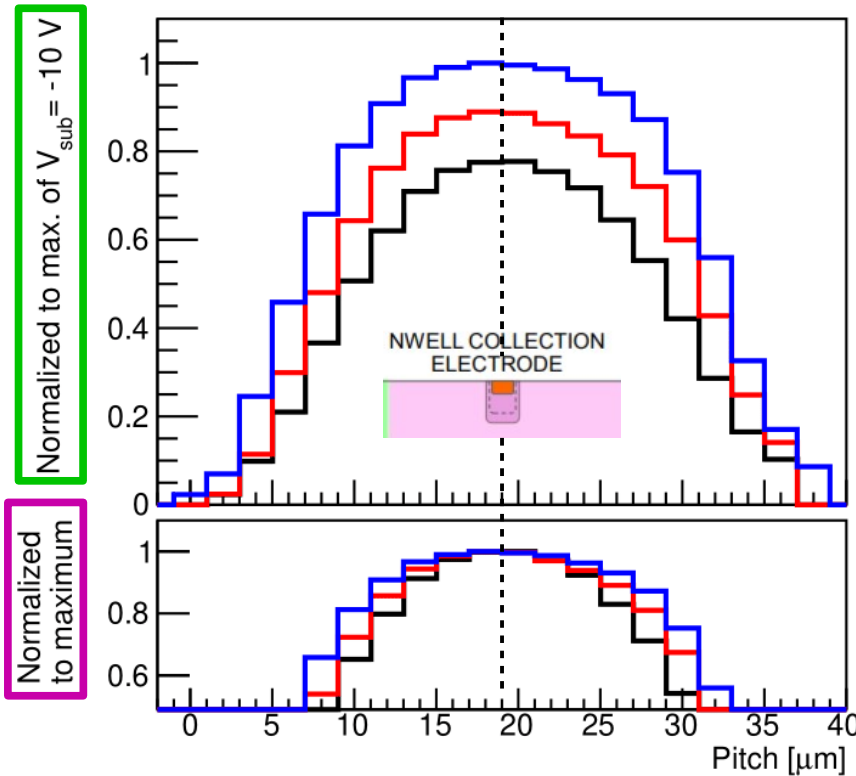


TCAD Simulations



M. Munker et al., JINST C05013

Taking a better look in pitch



MALTA2

EPI 30, 100 μm , L-dop, XDPW

- $V_{\text{sub}} = -6 \text{ V}$
FWHM = $23.6 \pm 0.2 \mu\text{m}$
- $V_{\text{sub}} = -8 \text{ V}$
FWHM = $24.4 \pm 0.2 \mu\text{m}$
- $V_{\text{sub}} = -10 \text{ V}$
FWHM = $25.0 \pm 0.2 \mu\text{m}$

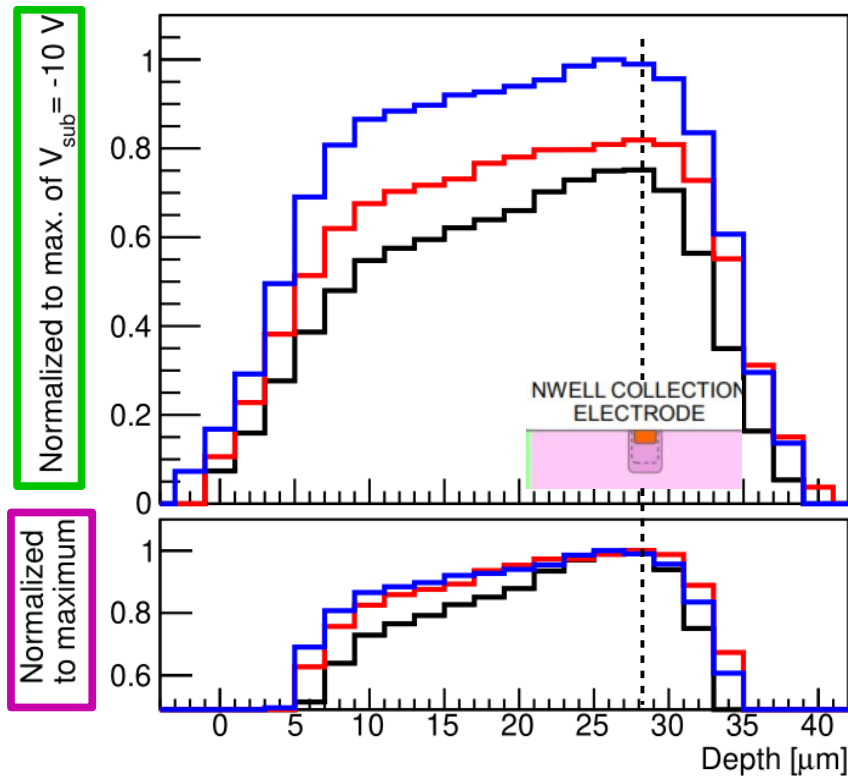
✗ Pitch and Depth projections: bias 8-10 V

- ◆ Normalization to max. bias -10 V
- ◆ Normalization to maximum
- ◆ FWHM \sim depletion size \oplus 4 μm beam width

✗ Pitch projection

- ◆ Symmetric around the collection electrode
- ◆ Lateral depletion increases with bias

Taking a better look in depth



MALTA2

EPI 30, 100 μm , L-dop, XDPW

- $V_{\text{sub}} = -6 \text{ V}$
; FWHM = $30.2 \pm 0.2 \mu\text{m}$
- $V_{\text{sub}} = -8 \text{ V}$
; FWHM = $29.8 \pm 0.2 \mu\text{m}$
- $V_{\text{sub}} = -10 \text{ V}$
FWHM = $30.0 \pm 0.2 \mu\text{m}$

✗ Pitch and Depth projections: bias 8-10 V

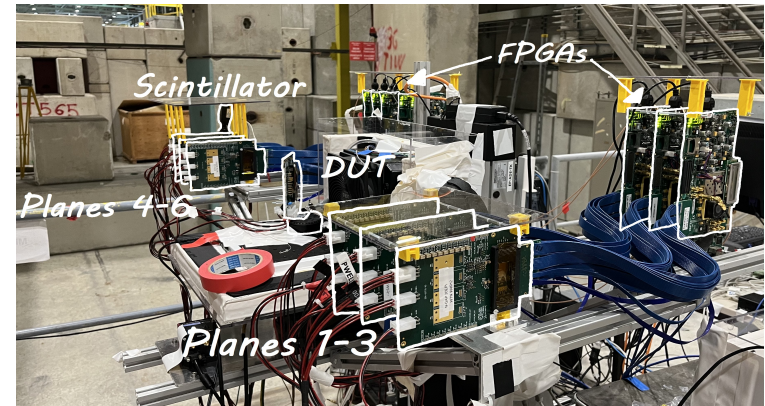
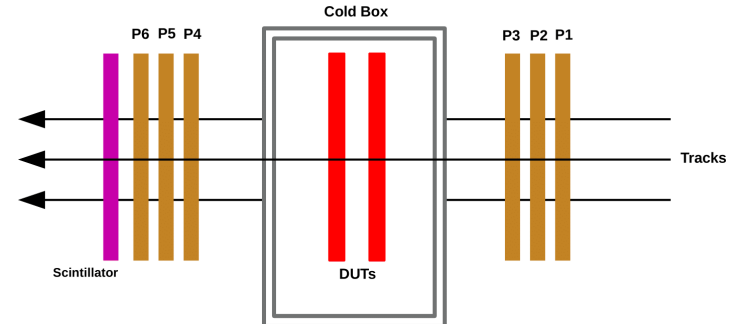
- ◆ Normalization to max. bias -10 V
- ◆ Normalization to maximum
- ◆ FWHM \sim depletion size \oplus 4 μm beam width

✗ Depth projection

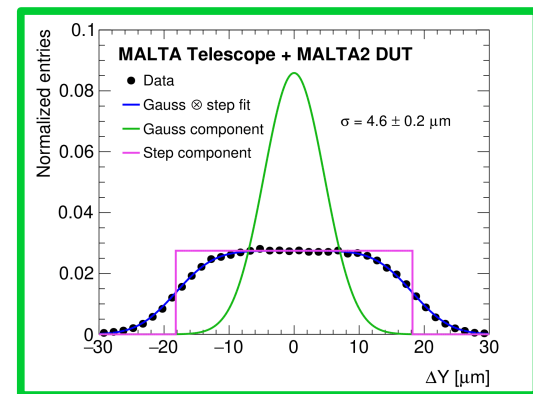
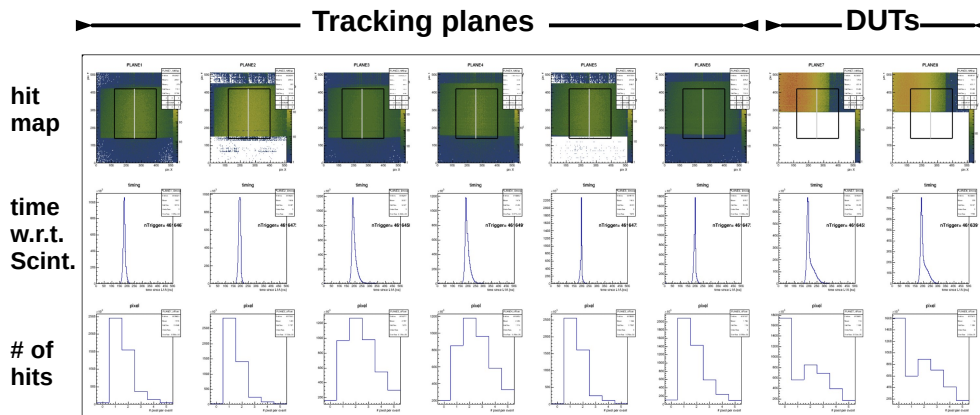
- ◆ Full depletion at -6 V bias
- ◆ “Flatter” distribution at higher bias

MALTA SPS Telescope

- X MALTA permanent fixture at CERN, SPS
 - ◆ 180 GeV hadron beam
 - ◆ 6 tracking planes: $<5 \mu\text{m}$ spatial resolution
 - ◆ Scintillator for precise time reference
 - ◆ Cold box: up to 2 DUTs + rotational stage
 - ◆ Flexible triggering configurations:
 - ◆ Users: BCM', ITk pixels, HGDT's LGAD
 - ◆ Online monitoring capability



M. van Rijnbach et al., EPJC 11760

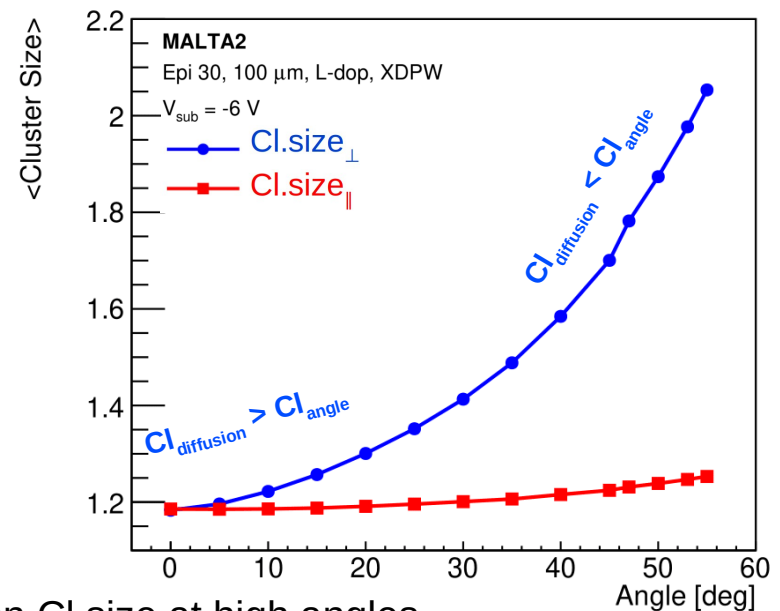
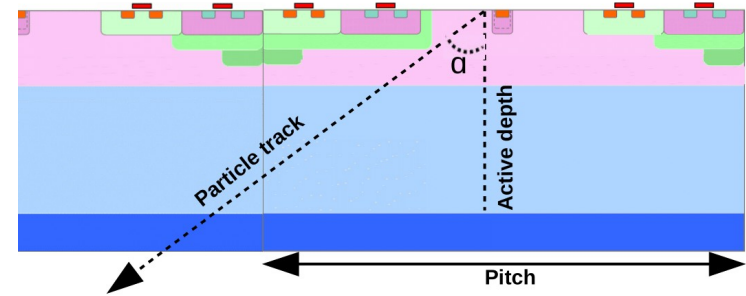


Grazing angle technique

$$Cl.size_{\perp}(\tan \alpha) = (d/p) \cdot \tan \alpha + Cl.size_{\perp}(0)$$

Geometrical model:

- ◆ $Cl.size_{\perp}$ – perpendicular to axis of rotation
- ◆ α – track angle
- ◆ p – pixel pitch
- ◆ d – measured active depth



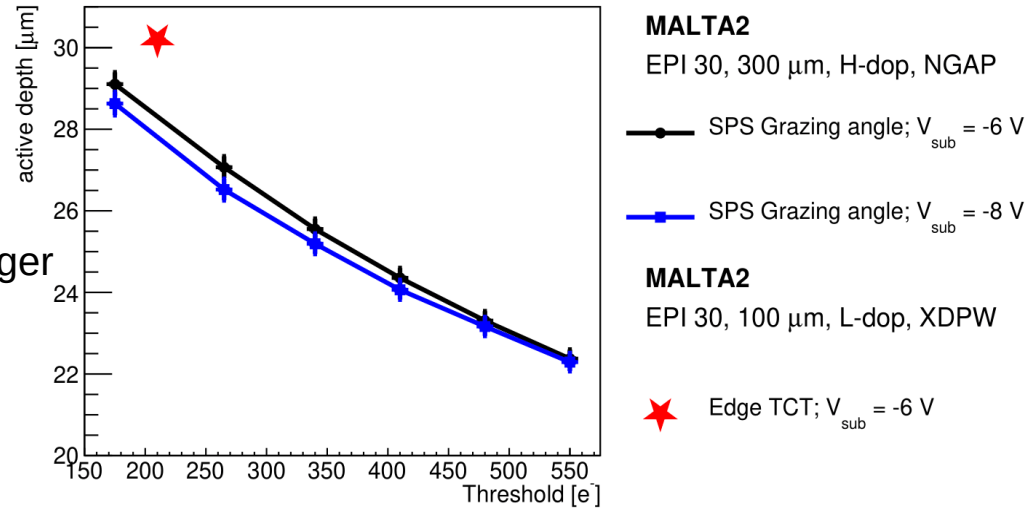
Model assumes a suppressed effect of diffusion Cl size at high angles

- ◆ $Cl.size_{\perp}$ ~ linear at high angles ($> 30^\circ$)
- ◆ $Cl.size_{\parallel}$ - no significant increase with angle

MALTA2 Epi sample

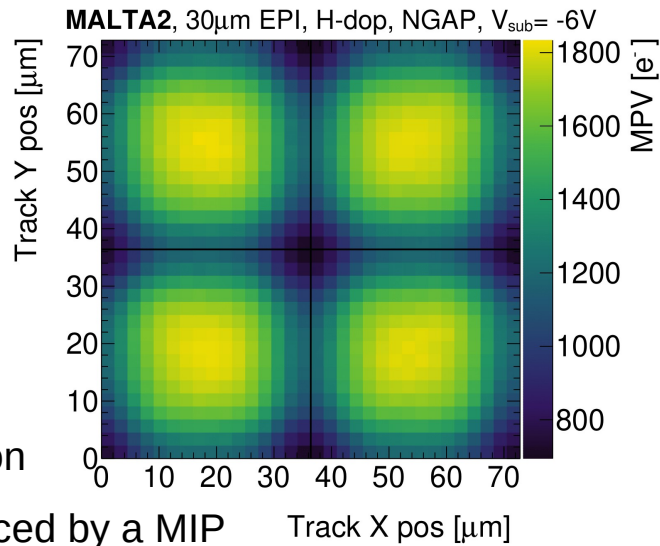
X E-TCT & grazing angle study:

- ◆ Active depth measured
- ◆ SPS threshold: pixel discriminator
- ◆ E-TCT threshold: oscilloscope trigger
- ◆ ~ no change in act. depth w/ bias
- ◆ Result match at lowest threshold



X Threshold dependence due to:

- ◆ Pixel boundary charge sharing
- ◆ Non-uniform in pixel charge collection
- ◆ Most Probable Value of charge induced by a MIP



Conclusions

- ✘ Two methods for investigating the active depth of the MALTA2 sensor
 - ◆ Edge Transient Current Technique (E-TCT):
 - ▶ Ability to scan the pixel in depth and pitch
 - ▶ Bypasses front end effects – independent study of pixel performance
 - ▶ Edge polish of sensors, PCB redesign
 - (100% laser availability)
 - ◆ Grazing Angle Technique:
 - ▶ “Easy” integration in a test beam experiment
 - ▶ Estimation of sensor performance behavior in a test beam environment
 - ▶ Tracking corrections; Front end effects; Sensitivity only in the depth axis

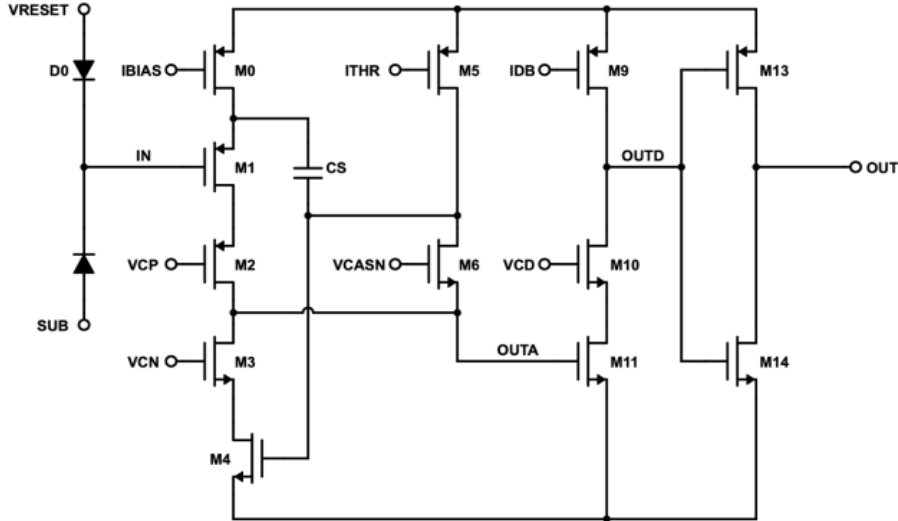
- ✘ Study of MALTA2:
 - ◆ Full depth depletion at -6 V bias: ~ 30 μm
 - ◆ Increase in lateral depletion with bias: 23.6 – 25 μm
 - ◆ Grazing angle study and E-TCT results compatible at the lowest threshold
 - ◆ A lot of nice results with MALTA2 in back-up

Thank you

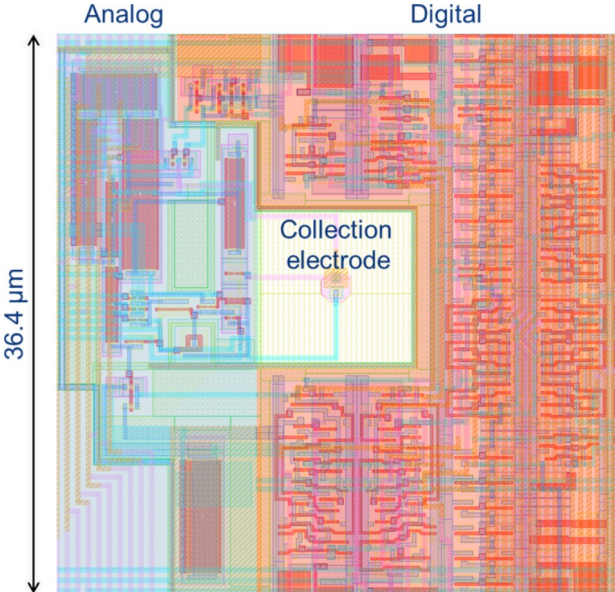


Backup

Pixel layout



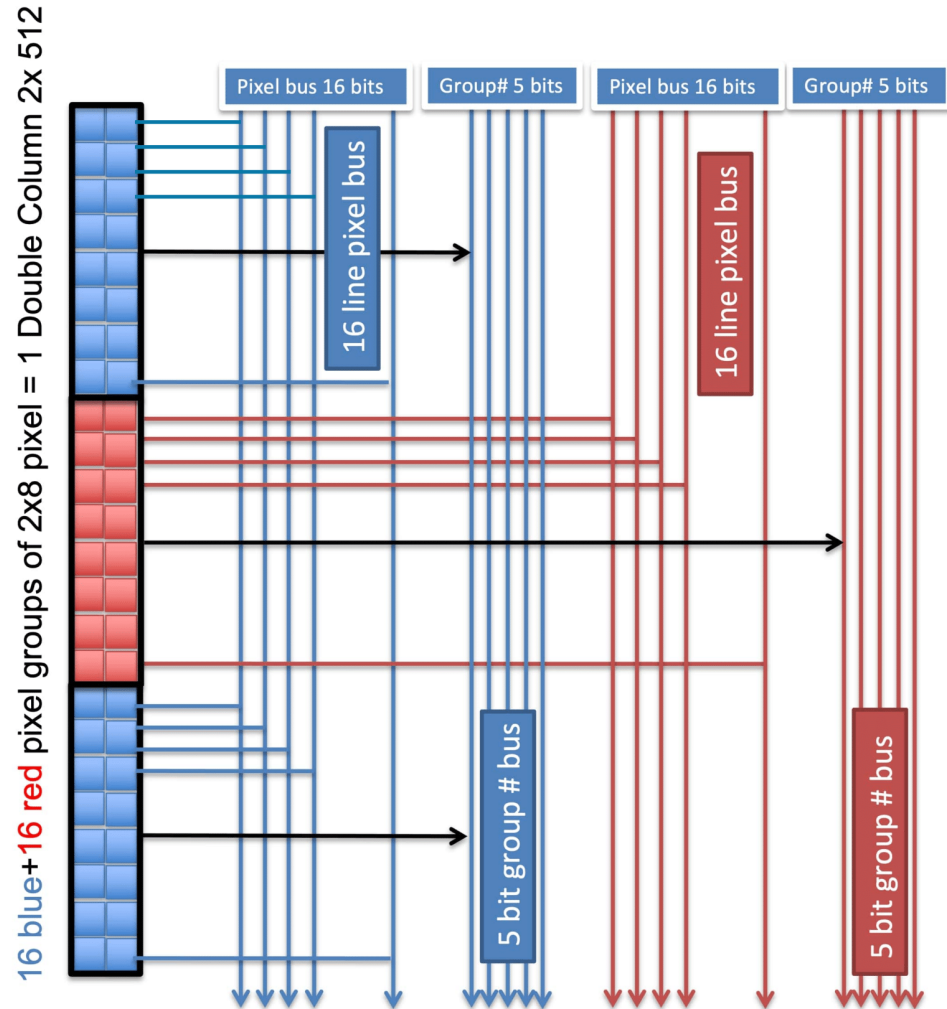
MALTA2 cascoded FE



MALTA2 pixel

MALTA Double Column Architecture

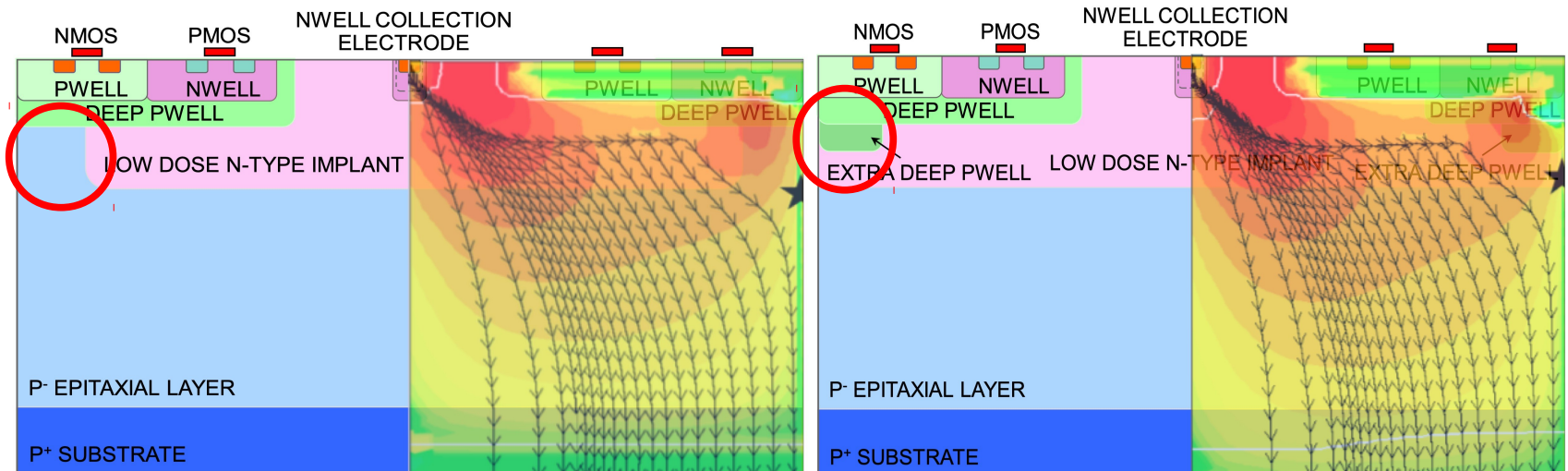
- ✘ Double column readout
 - ◆ 2 x 8 pixel group is read out after one detects charge above threshold
 - ◆ Neighboring groups are read out on different double columns: odd and even



MALTA process modifications

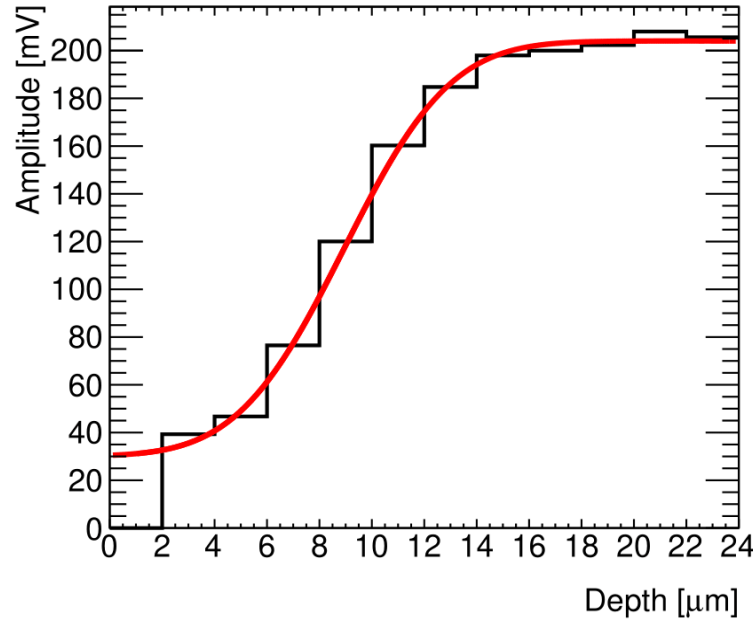
X Process modifications to enhance the electric field

- ◆ Gap in the low doping n-layer (NGAP)
- ◆ Extra deep p-well implants (XDPW)



Focus finding

Turn on curve →
Laser width



MALTA2,

EPI 30, 100 μm , L-dop, XDPW

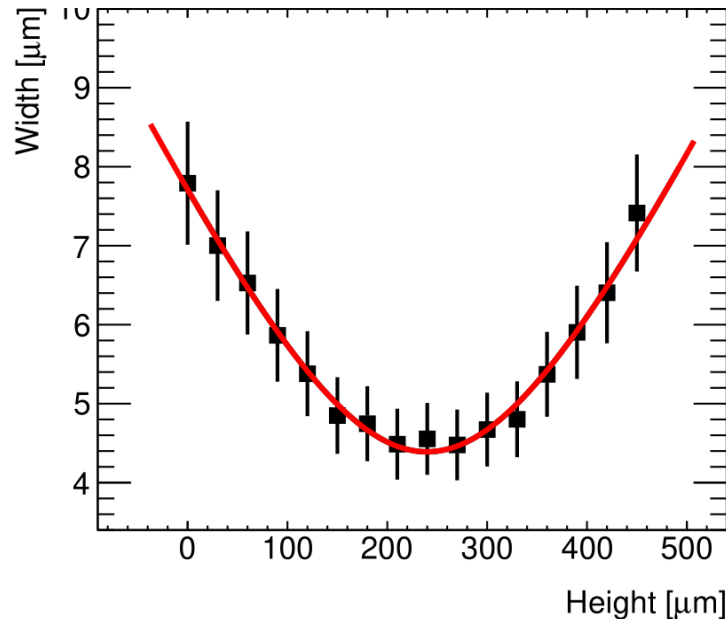
$V_{\text{sub}} = -6 \text{ V}$

$f(x) = a * (\text{Erf}((x-b)/c) + 1)$

Beam width = 6.4

Height = 100 μm

Polynomial fit of width
vs height → best focus
point



MALTA2,

EPI 30, 100 μm , L-dop, XDPW

$V_{\text{sub}} = -6 \text{ V}$

$w(z) = w_0 \sqrt{1 + \left(\frac{z-z_0}{z_R}\right)^2}$

Minimum spot size: $w_0 = 4.37 \mu\text{m}$

Rayleigh length: $z_R = 163.32 \mu\text{m}$

MALTA2 radiation hardness

X Three neutron irradiation doses:

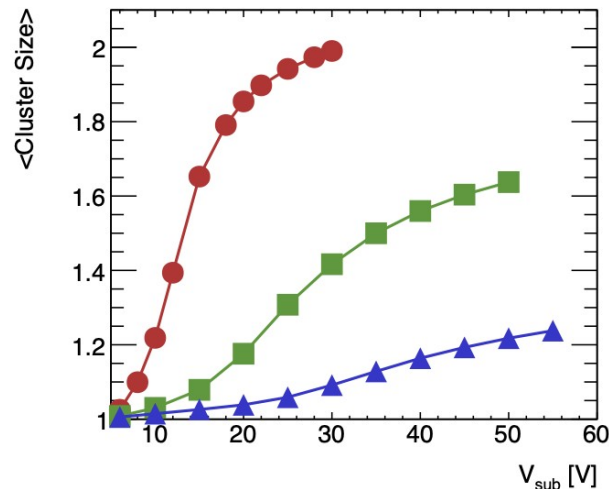
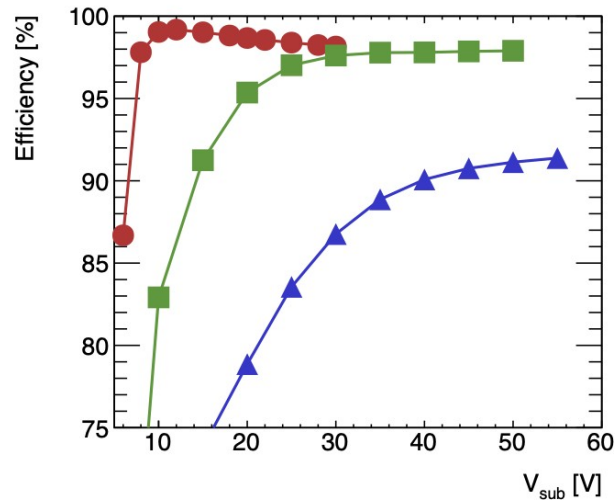
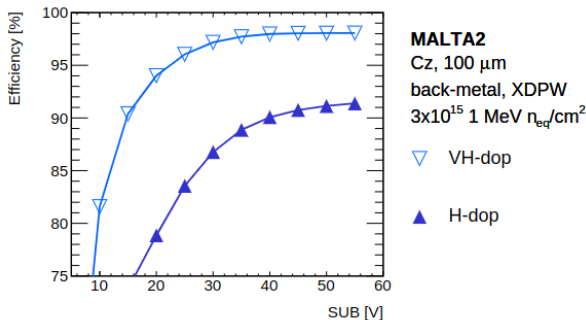
- ◆ $1 \times 10^{15} \text{ n}_{\text{eq}} / \text{cm}^2$
- ◆ $2 \times 10^{15} \text{ n}_{\text{eq}} / \text{cm}^2$
- ◆ $3 \times 10^{15} \text{ n}_{\text{eq}} / \text{cm}^2$

X Efficiency

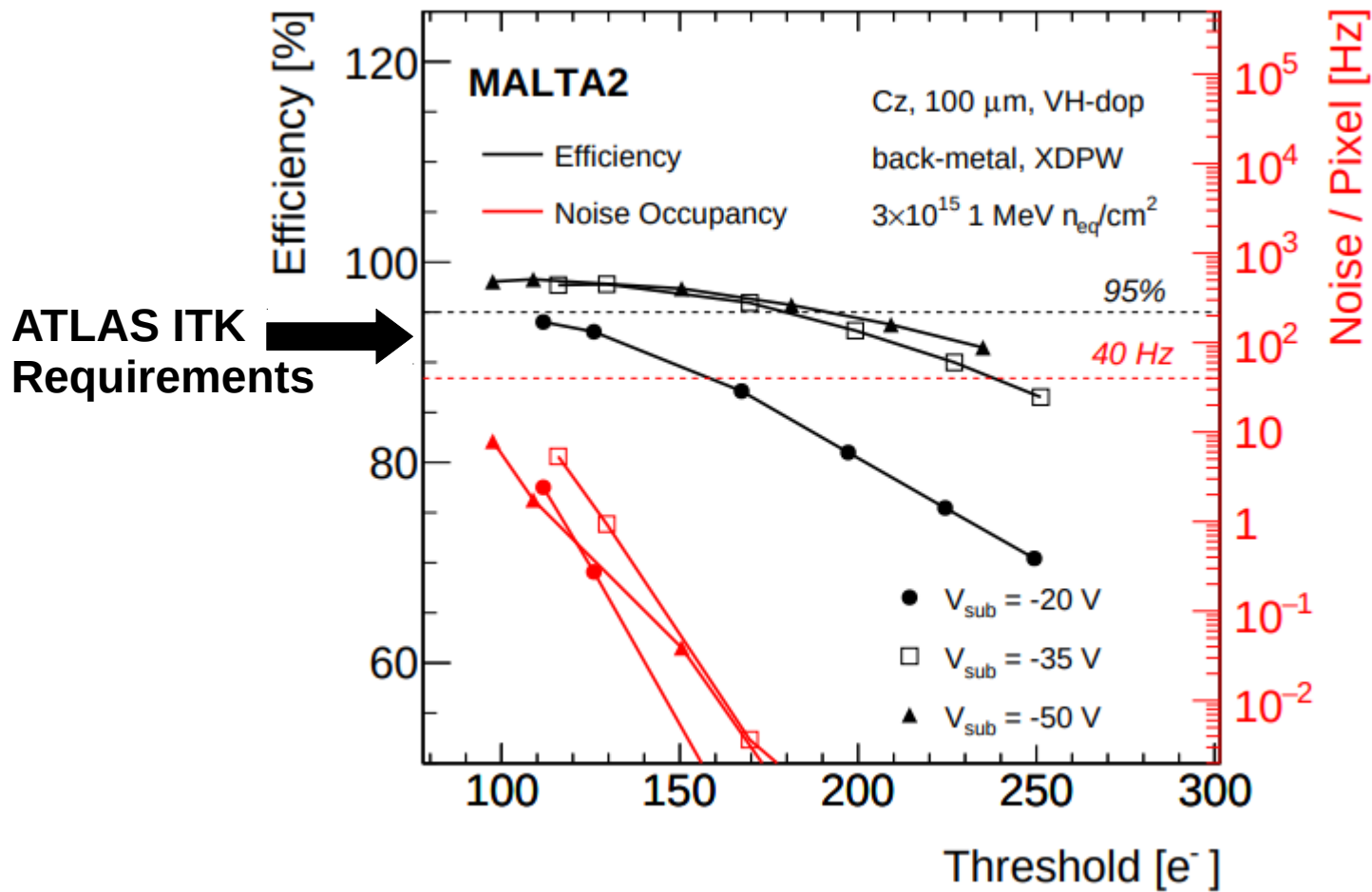
- ◆ Efficiency drop at lower V_{sub}
- ◆ >95% eff. recovered for 1;2;3 $\times 10^{15} \text{ n}_{\text{eq}} / \text{cm}^2$

X Cluster size

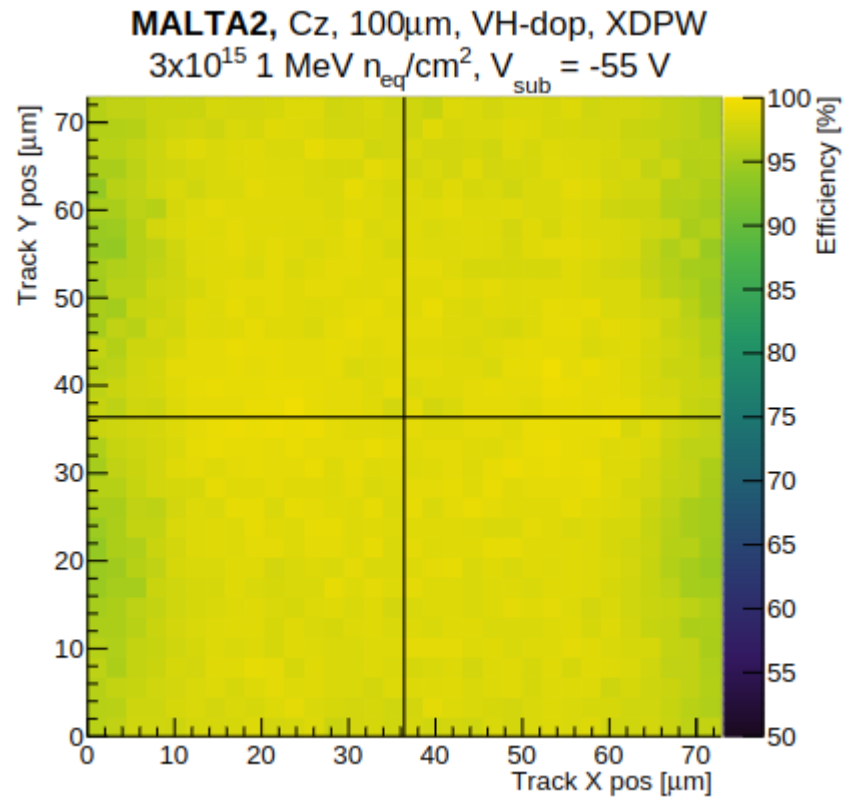
- ◆ Cl. size. ~ 1 at low V_{sub}
- ◆ Increase with higher V_{sub}



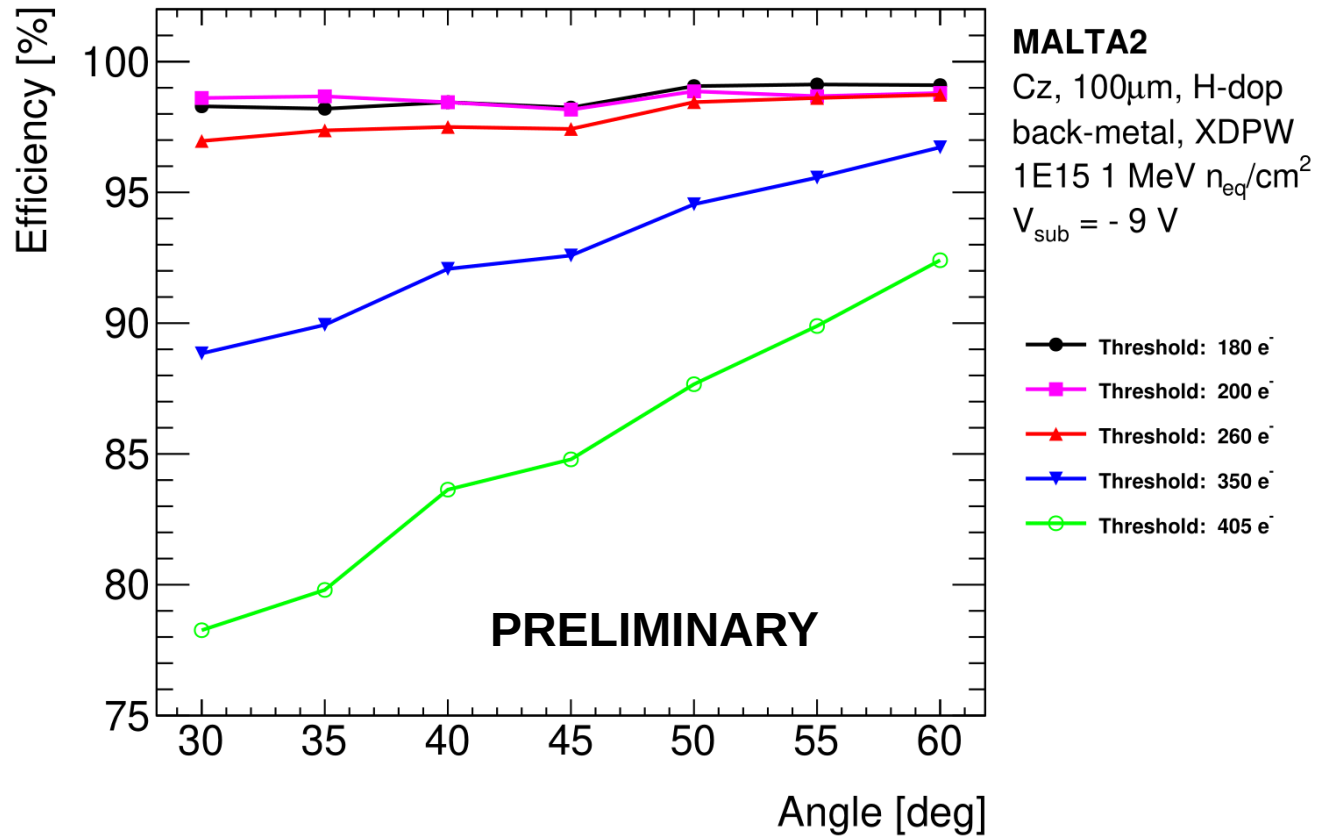
Efficiency after irradiation



In pixel eff. after 3E15 irradiation



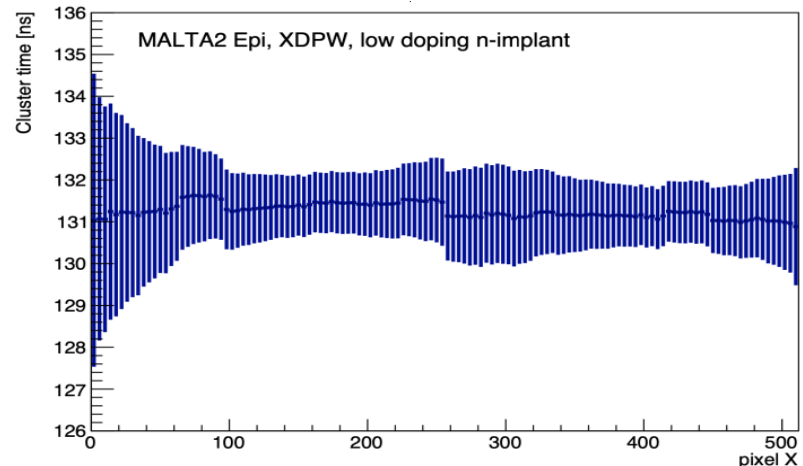
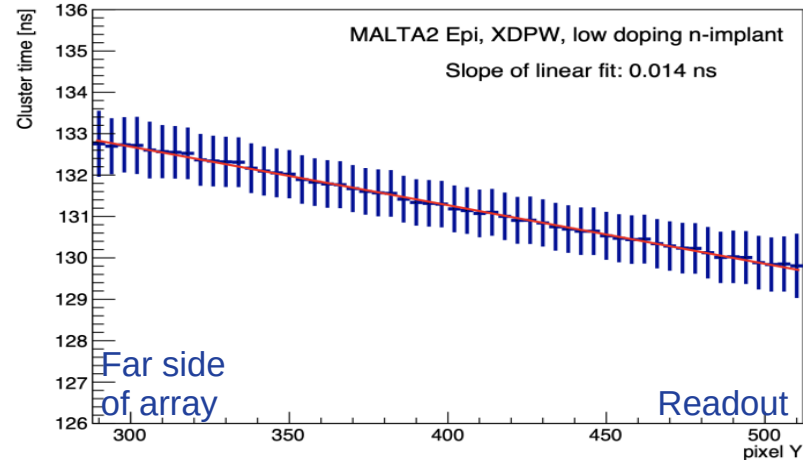
Efficiency after irradiation



MALTA2 Timing corrections

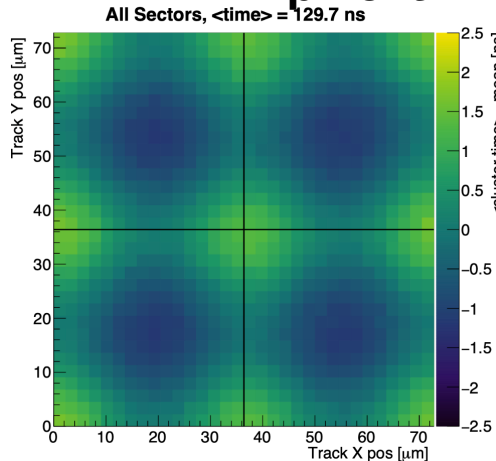
Time of arrival of the fastest hit in a matched cluster w.r.t scintillator reference, as a function of the matrix X/Y coordinate

- **Timing corrections:**
 - **(Y)** Linear due to column time propagation (**top**)
 - **(X)** Non-uniform chip response in the row direction (**bottom**)
- The **timing plots** are a convolution of:
 - Electronics jitter
 - Time-walk
 - Charge collection effects
 - Scintillator jitter (500ps)
 - FPGA readout jitter (900ps)

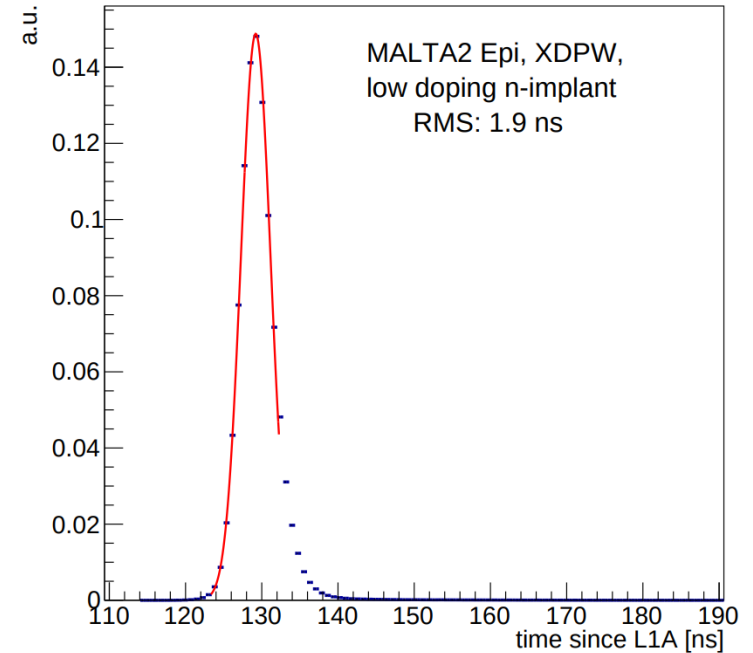


MALTA2 timing

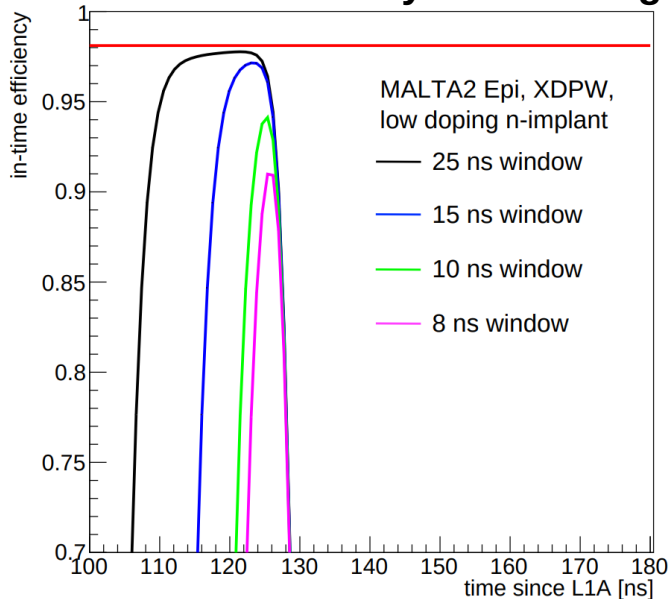
MALTA2 in-pixel timing



MALTA2 Time of arrival of a hit in a cluster w.r.t scintillator ref.

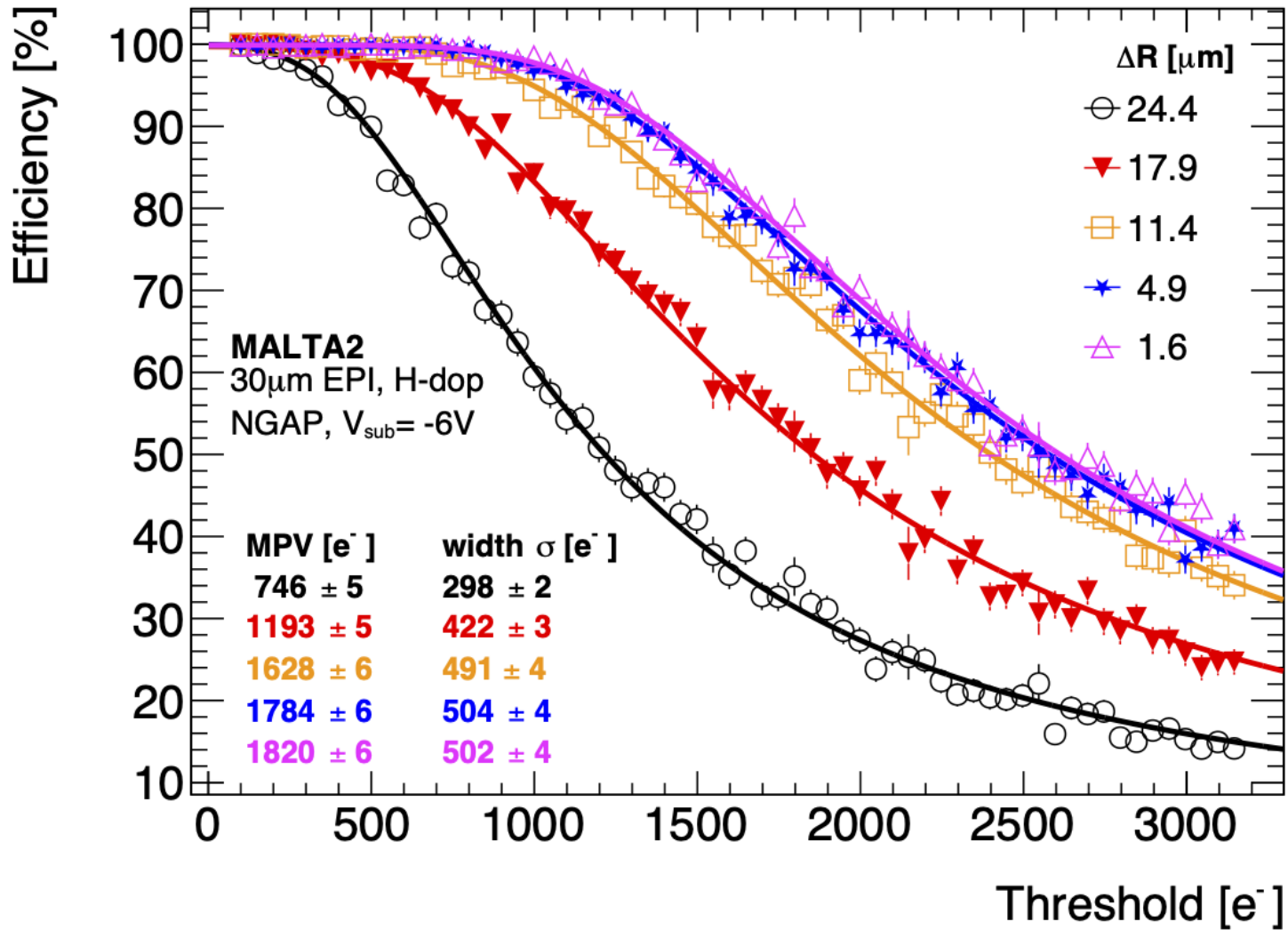


MALTA2 in-time efficiency for a sliding window

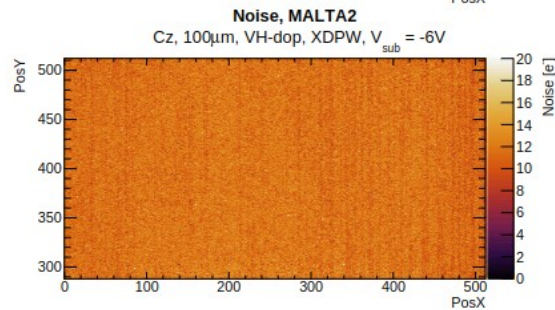
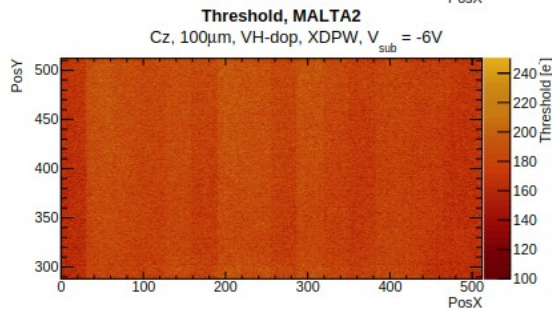
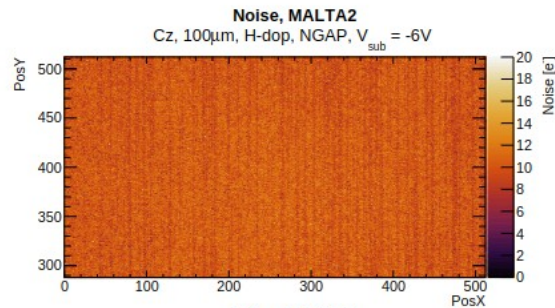
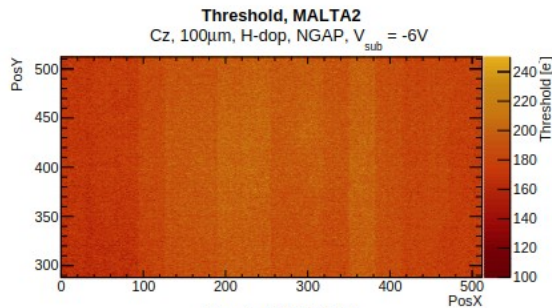
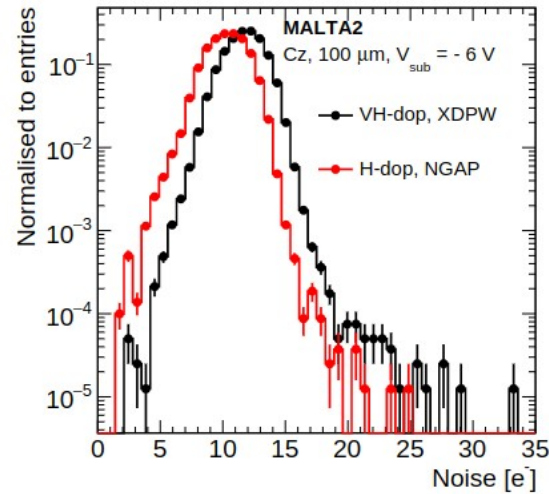
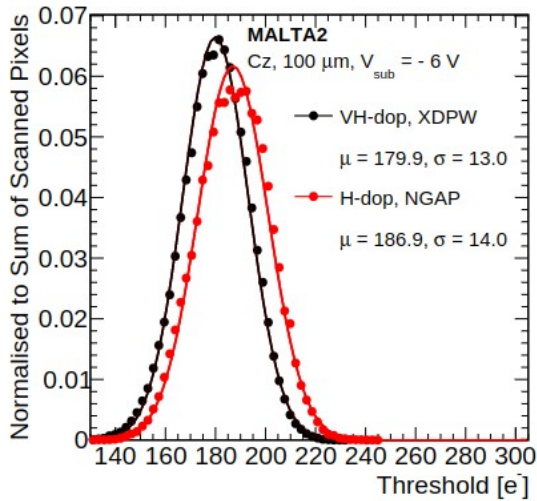


- >98% of signals within 25ns; >90% in-time efficiency for 8ns window
- Pixel corners generate late-arriving signals; <2 ns timing resolution
- The timing plots are a convolution of:
 - Electronics jitter, sampling readout jitter, scintillator jitter
 - Time-walk
 - Charge collection effects

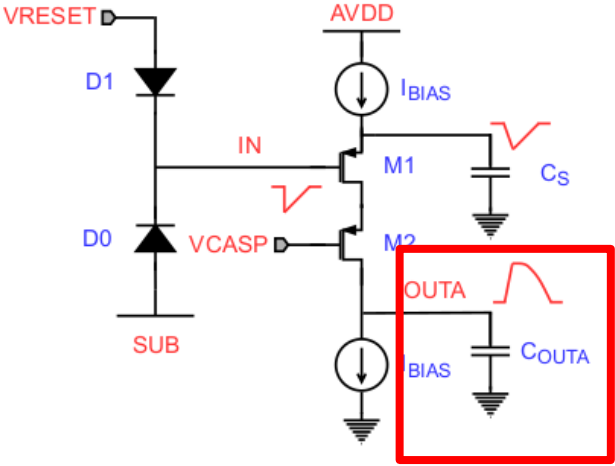
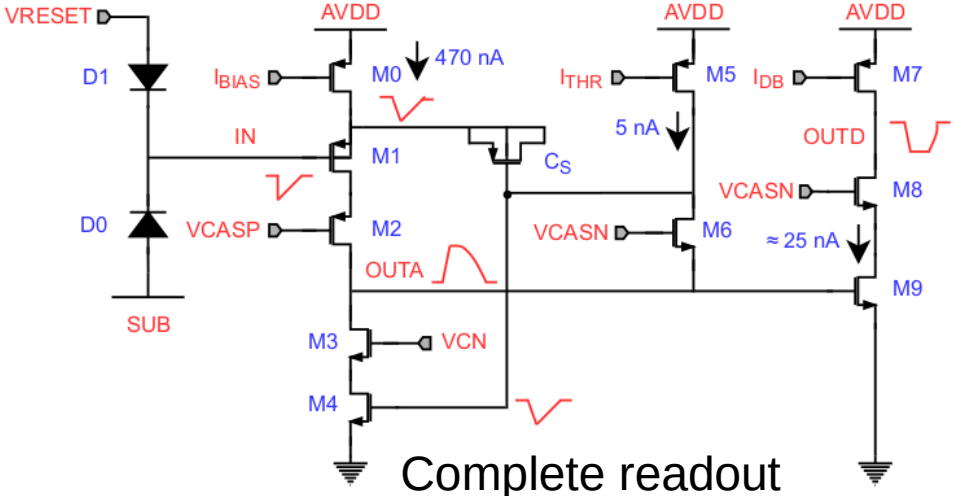
MPV derivation



MALTA2 Threshold and noise operation



Analog monitoring

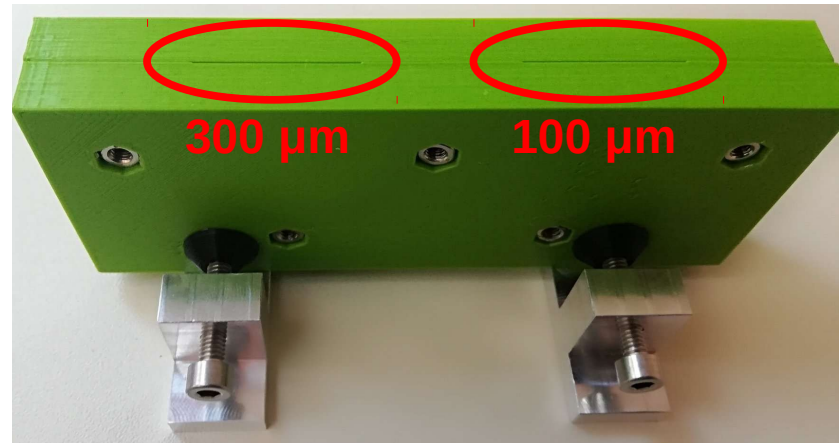


Simplified analog output schematic

Edge polishing

X 3D printed piece to hold up to 2 sensors:

- ◆ 100 μm thick (EPI)
- ◆ 300 μm thick (Cz)



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